

Optimizing Base Layer Design Rule Checks in Chip Physical Design

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Abstract: *This article presents a comprehensive analysis of abstract modeling approaches for base layer design rule checks in advanced semiconductor design. As semiconductor technology continues to advance toward smaller nodes, the complexity of base layer design rules has grown exponentially, presenting significant challenges in verification and implementation. The article examines the evolution of design rule complexity, current implementation challenges, and the emergence of abstract modeling as a solution. The article explores how abstract modeling, enhanced by machine learning and artificial intelligence, can improve design quality, reduce verification time, and optimize resource utilization. The article also investigates the implementation considerations for advanced nodes, including computational resource management, design flexibility, and manufacturing requirements integration. Through analysis of multiple case studies and industry data, the article demonstrates how abstract modeling methodologies can significantly improve design efficiency, reduce costs, and enhance manufacturing yields in advanced semiconductor processes.*

Keywords: Abstract Modeling, Base Layer Design Rules, Semiconductor Design, Design Rule Checks, Physical Design Automation, Machine Learning Optimization, Advanced Node Technology

